

369520919

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1 IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

2 Priority APPLICATION SERIAL NO. 08/984,730
3 Priority FILING DATE December 4, 1997
4 INVENTORSHIP D.G. Custer et al.
5 ASSIGNEE Micron Technology, Inc.
6 Priority GROUP ART UNIT 3723
7 Priority EXAMINER L. Wilson
8 ATTORNEY'S DOCKET NO. MI22-1172
9 TITLE: Polishing Systems, Methods of Polishing Substrates, and Methods of Preparing
10 Liquids for Semiconductor Fabrication Processes

11 Assistant Commissioner for Patents
12 Washington, D. C. 20231
13 Attention: Official Draftsman

14 **SUBSTITUTE DRAWING REQUEST**

15 Please enter the enclosed substitute drawings in the above-referenced
16 application in place of drawings originally filed. The content of the drawings are
17 identical to those now on file in this application.

18 Acknowledgment of receipt of the formal drawings and their acceptance into
19 the file is requested.

20 Respectfully submitted,

21 Date: 4/22/99

22 By:

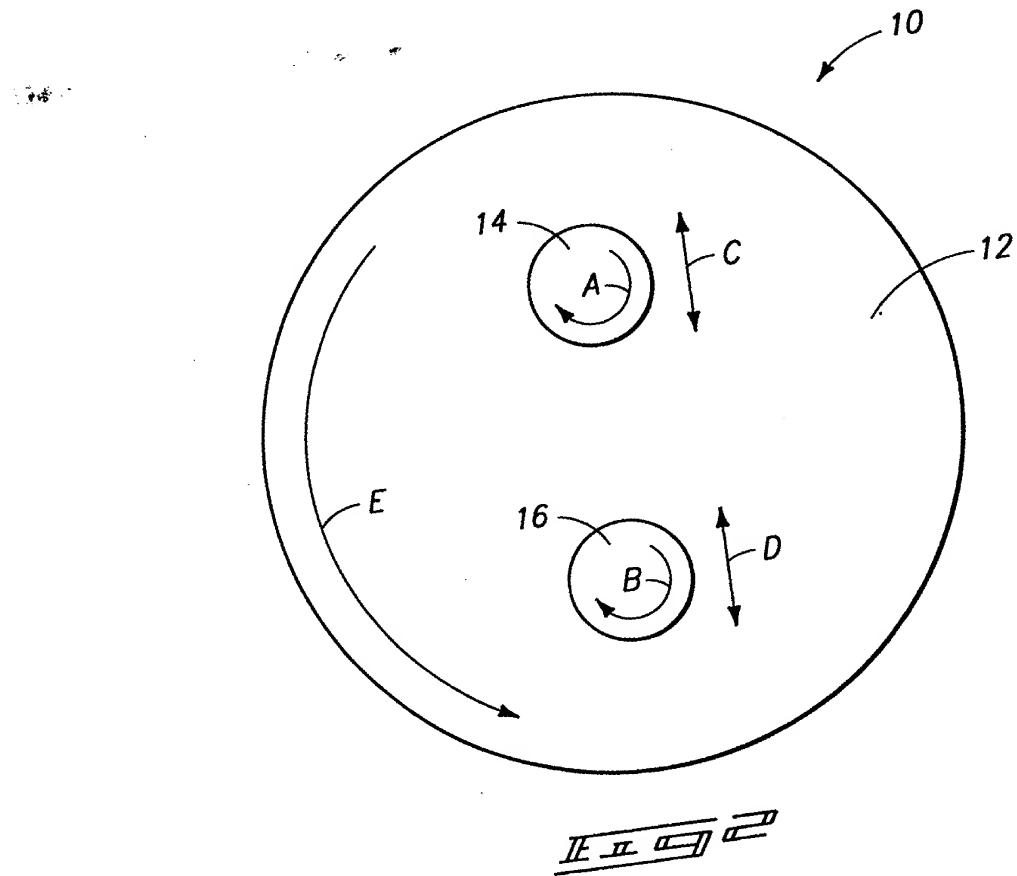
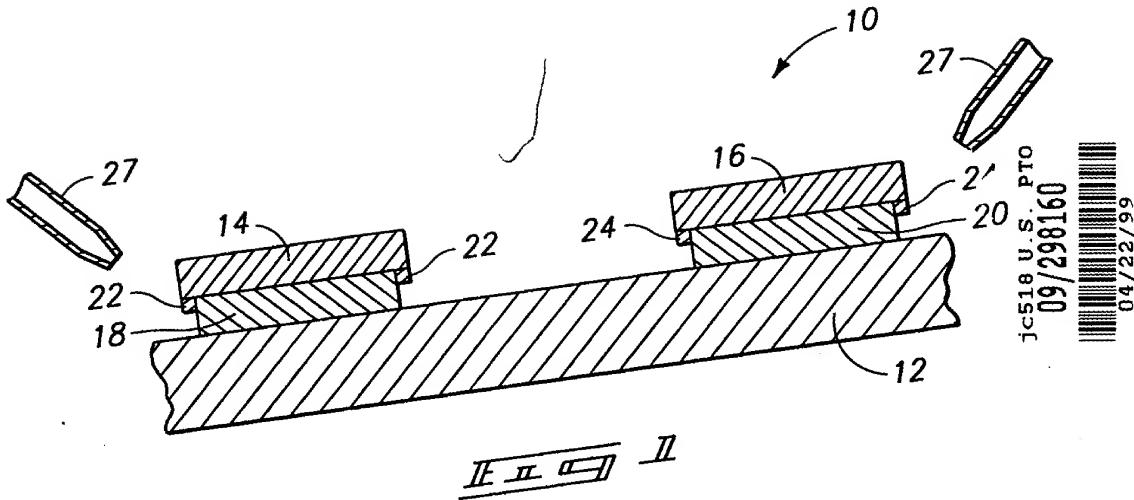

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30 Enclosures: 2 Sheets of Formal Drawings, Figs. 1-3.

MI22-775

AS FILED

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AS FILED

